

Hwang, Wan Sik (Ph. D. Student) won the DPS 2005 Young Research Award at 27<sup>th</sup> International Symposium on Dry Process, for the paper entitled “Effect of SiO<sub>2</sub> Mask on Surface Properties of Advanced Gate Stacks using ICP of Cl<sub>2</sub> / HBr.

Hwang, Wan Sik was born in Seoul, South Korea, in 1975. He received the bachelor and master of engineering degree in materials engineering from Hankuk Aviation University, Korea, in 2001 and 2003 respectively. He worked as an assistant researcher at NANO Bio-mechatronics Research Center in Korea Electronics Technology Institute (KETI), Korea. Currently, he is pursuing Ph.D. degree with Silicon Nano Device Lab (SNDL), department of electrical and computer engineering, National University of Singapore.

He has authored or co-authored 20 internationally referred journals and conference proceedings while pursuing Ph.D. He received Dorothy M. and Earl S. Hoffman Travel Grants at AVS 52<sup>nd</sup> International Symposium, Boston, USA, 2005.

Dry processes are the state of the art technologies leading the way through ultra-high performance in microelectronic devices. The DPS Young Researcher Award is given to recognize excellence among the contributing papers based on scientific relevance. He will make an Award Presentation at DPS 2006 in Nagoya, Japan, on November 2006